

STS Etch Rates Are All in Angstroms / min

Films	PECVD Nitride-340	PECVD Oxide-340	Thermal Oxide	Low Stress Nitride	Regular Nitride	Resist 1813	Resist 1818	Bare Silicon Wafer
Recipes								
nit1.set	2173	370	326	801	737	771	736	1536
nit2.set	1616	147	148	437	94	366		730
nit3.set	818	45	43	140	94	142		514
fastpoly.set	2350	279	216	640	880	376	600	12853
pjsnitd1.set	2090	586	572	213	1243	132		3756
slowpoly.set	731	70	38	22	250	140		5050
tyb-test.set	149	336	317	99	230	60		367
pjsoxide.set	161	331	303	224	220	124	93	92
O2clean.set						1500	1450	-4

All etch rates were taken with a single wafer after a 15 min clean and a 2 min coating etch.

Remember these values are only to be used as a guide, you must verify results yourself.